

REMARKS / ARGUMENTS

The present paper is in response to the Office Action mailed September 22, 2003, in which Claims 1 through 29 were rejected. Applicants have thoroughly reviewed the outstanding Office Action including the Examiner's remarks and the reference cited therein. The following remarks are believed to be fully responsive to the Office Action and are believed to render all claims at issue patentably distinguishable over the cited references.

No claim is amended herein. No claim is cancelled. No claim is added. Accordingly, Claims 1 through 29 remain pending.

Applicants respectfully request reconsideration in light of the following remarks.

CLAIM REJECTIONS – 35 U.S.C. SECTION 103(a)

The Examiner rejected Claims 1 through 29 under 35 U.S.C. Section 103(a) as being Unpatentable over Hirukawa (2003/0103196) in view of Hirukawa et al. (U.S. 5,703,675). Of the rejected claims, only Claims 1, 6 and 18 are independent.

Applicants respectfully traverse this rejection.

This rejection is respectfully traversed on the basis that neither Hirukawa (2003/0103196) nor Hirukawa et al. (U.S. 5,703,675) disclose or suggest every element of the claimed invention. The combination of Hirukawa (2003/0103196) and Hirukawa et al. (U.S. 5,703,675) actually also fails to teach or suggest every element of the claimed invention. Moreover, the proposed modification of

Hirukawa (2003/0103196) and Hirukawa et al. (U.S. 5,703,675) would change their principles of operation. Thus the combination of Hirukawa (2003/0103196) and Hirukawa et al. (U.S. 5,703,675) is insufficient to render the claimed invention unpatentable.

Particularly, Hirukawa (2003/0103196) discloses an exposure method and an exposure apparatus. FIG. 1 of Hirukawa (2003/0103196) shows the exposure apparatus. The exposure method of Hirukawa (2003/0103196) includes a two-step pattern transfer to reduce the random error at the time of exposure and form fine pattern with a good accuracy. The exposure method of Hirukawa (2003/0103196) also reduces the changes in line widths of device patterns due to defocus and realize line widths close to the line widths in the case of exposure by the best focus for all patterns.

As described in paragraph 0100 to 0138 of Hirukawa (2003/0103196), the exposure method of Hirukawa (2003/0103196) uses the first reticle R1 with reticle patterns comprised of dense patterns 41a of shapes corresponding to the dense patterns 41c of the device patterns and dense patterns similar to the dense patterns 41a formed by patterns 42a of shapes corresponding to the isolated patterns 42c of the device patterns plus a plurality of auxiliary patterns 43a in their vicinity as shown in FIG. 2A to 2C of Hirukawa (2003/0103196).

The exposure method of Hirukawa (2003/0103196) also uses the second reticle R2 having reticle patterns comprised of dense patterns 41b of shapes corresponding to the dense patterns 41c of the device patterns and

isolated patterns 42b of shapes corresponding to the isolated patterns 42c of the device patterns as shown in FIG. 2A to 2C of Hirukawa (2003/0103196). Hirukawa (2003/0103196) actually discloses a photomask or reticle (R2) with a dense pattern and an isolated pattern as Hirukawa et al. (U.S. 5,703,675) dose.

However, the exposure method of Hirukawa (2003/0103196) must uses two reticles with different or same patterns to expose twice so that the random error at the time of exposure can be reduced and fine pattern with a good accuracy can be obtained. Furthermore, the changes in line widths of device patterns due to defocus can be reduced and line widths close to the line widths in the case of exposure by the best focus for all patterns can be realized. For example, the dense patterns 41c and the isolated patterns 42c of the device patterns with sharp line widths as shown in FIG. 2C must be formed by two exposure steps each with half total amount of exposure. One exposure step transfers the dense patterns 41a of shapes and the patterns 42a of shapes plus a plurality of auxiliary patterns 43a in their vicinity of the first reticle R1 with half total amount of exposure onto the photoresist layer. This exposure step would not render the photoresist layer developable since only half total amount of exposure energy is received. The other exposure step transfers the dense patterns 41b of shapes and the patterns 42b of shapes of the first reticle R2 with half total amount of exposure onto the photoresist layer. After a developing process, the dense patterns 41c and the isolated patterns 42c of the device patterns are formed. It is quite clear that the exposure method of Hirukawa (2003/0103196) must uses

two reticles with different or same patterns and two exposure steps each with half total amount of exposure energy to form device patterns with fine line widths and good accuracy.

Hirukawa et al. (U.S. 5,703,675) discloses a projection-exposing apparatus having a mask which has a pattern formed with a pitch P_R , an illuminating optical system for applying illuminating light from a light source to the mask, a projection optical system for projecting an image of the pattern onto a photosensitive substrate, and a deflecting grating member formed with a pitch P_G disposed between the light source and the pattern of the mask for generating diffracted light. The pitch P_G of the deflecting grating member is defined in the relation $P_G = 2P_R$. Hirukawa et al. (U.S. 5,703,675) only discloses a photomask or reticle with a dense pattern and an isolated pattern and the teaching of Hirukawa et al. (U.S. 5,703,675) is not sufficient to render the claimed invention prima facie obvious under Hirukawa (2003/0103196).

Thus the combination of Hirukawa (2003/0103196) and Hirukawa et al. (U.S. 5,703,675) is insufficient to render the claimed invention unpatentable. Reconsideration and withdrawal of the rejections under 35 U.S.C. Section 103(a) are respectfully requested.

CONCLUSION

In light of the above remarks, Applicants respectfully submit that all pending Claims 1 through 29 as currently presented are in condition for allowance. If, for

Appl. No. 10/033,891

Amdt. dated January 28, 2004

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any reason, the Examiner disagrees, please call the undersigned attorney at 248-433-7552 in an effort to resolve any matter still outstanding *before* issuing another action. The undersigned attorney is confident that any issue which might remain can readily be worked out by telephone.

Applicants respectfully request that a timely Notice of Allowance be issued in this case.

Respectfully submitted,



Thomas T. Moga
Registration No. 34,881
Attorney for Applicants

DICKINSON WRIGHT PLLC
1901 L Street, N.W., Suite 800
Washington, D.C. 20036
202-457-0160

Dated: **January 28, 2004**

TTM/hs